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L4	31	(local adj flare) and (mask or photomask) and (lithograph$3 or photolithograph$3) and (proximity or correction or opc)	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2008/06/30 17:48
L5	302	L3 and @ad<"20031001"	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2008/06/30 17:52
L6	147	L3 and average and @ad<"20031001"	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2008/06/30 18:06

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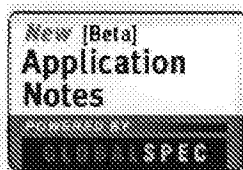
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